

PLASMA DEPOSITION OF SPIN CHUCKS TO REDUCE
CONTAMINATION OF SILICON WAFERS

ABSTRACT

An apparatus for delivering a fluidic media to a wafer includes a housing defining a process chamber. A fluidic media delivery member is coupled to the process chamber. A rotatable chuck is positioned in the process chamber. The rotatable chuck has a wafer support surface coated with a coating material. A vacuum supply line is coupled to the rotatable chuck.